

ABSTRACT

A positive resist mainly composed of a novolak resin and comprising a naphthoquinone diazido-based photosensitizer as an energy beam sensitive resin (e.g., a photosensitive resin) is applied in a thickness of 0.1 to 0.2 μm to a surface of a glass substrate 1 provided with transparent electrodes and dried so as to form a photosensitive film. Next, using a mask, the film is exposed to ultraviolet rays (365 nm). Then, moisture in the air reacts with the resist in an exposed portion 2', thereby generating -COOH groups, with which $\text{CH}_3(\text{CH}_2)_{18}\text{SiCl}_3$ is allowed to react so as to cause a dehydrochlorination reaction, thereby forming a monomolecular chemisorption film 6 comprising carbon chains 8. This film is used as an alignment film. Thus, the present invention provides a method for producing a uniform and thin alignment film for use in a liquid crystal display panel with a high efficiency without performing a rubbing treatment, and a method for producing a display panel using the same.